

Call for Paper

17th International WorkShop on New Group IV Semiconductor Nanoelectronics

Nov. 9(Mon.) - 10(Tue.), 2026

<http://www.murota.riec.tohoku.ac.jp/EI4GroupIV-WS2026/>

Sakura Hall, Katahira Campus,
Tohoku University, SENDAI, JAPAN

The 17th International Workshop on New Group IV Semiconductor Nanoelectronics will be held in Sakura Hall, Katahira Campus, Tohoku University, Sendai, Japan, on November 9-10, 2026. This workshop will focus on new group IV semiconductor nanoelectronics.

SCOPE

- Si, Ge, Si-Ge, Si-Ge-C, Si-Ge-Sn, Si-C, Other Group IV Materials and Their Heterostructures
- Thin Film Formation, Crystal Growth and Doping Techniques of Molecular Beam Epitaxy, Chemical Vapor Deposition and Other Novel Growth
- Wet and Dry Etching Process
- Formation and Evaluation of Heterojunction, pn Junction and Other Junctions with Insulators and Metals
- Self-Organized and Self-Aligned Process
- Quantum Well, Wire and Dot (1D, 2D and 3D Confined) Structure Formation Techniques
- Thin Film and Wafer Bonding Techniques
- Evaluation of Electronic and Crystallographic Structures
- Electronic and Optical Device Applications
- Process Technology for High-Performance Devices and Integrated Circuits

SUBMISSION OF ABSTRACTS

Submission Deadline : October 8, 2026

PDF or MS Word file of abstract (one or two pages, typically one-page main text and one-page figures), written in English on white bond paper (A4 size; 2.5cm margin on four sides), should be submitted to the Secretariat at the CORRESPONDENCE address. All the accepted abstracts will be expected to be opened on the workshop web site. The abstract should be headed by the title, author(s), affiliation(s), address, telephone number and e-mail address, and clearly describe the originality and new contributions of the work. The title, author(s), affiliation(s), address, telephone number and e-mail address should be also sent by E-mail to

EI4GroupIV@gmail.com

Papers to be presented at the workshop will be selected by the Program Committee based on the submitted abstracts. The notice of acceptance will be e-mailed to the first author or corresponding author within a few days.

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REGISTRATION

The registration desk will be open tentatively for
08:30 - 16:30 on Monday, Nov. 9, 2026,
08:30 - 16:30 on Tuesday, Nov. 10, 2026.

Your completed registration form should be sent to Secretariat by e-mail for advanced registration.

CORRESPONDENCE

Secretariat of International WorkShop on New Group IV Semiconductor Nanoelectronics,
Research Institute of Electrical Communication,
Tohoku University
2-1-1, Katahira, Aoba-ku, Sendai, 980-8577, Japan
Tel: +81-(0)90-7060-7194
E-mail: **EI4GroupIV@gmail.com**